



[TuC1] Advanced Metrology & Inspection, Process Diagnostics & Control, and Yield Management I

Session Date	November 11 (Tue.), 2025
Session Time	13:00-14:45
Session Room	Room C (Grand Ballroom 3, 2F)
Session Chair	Dr. Byoung-Ho Lee (Hitachi High-Tech Corp., Japan)

[TuC1-1] [Plenary] 13:00-13:45

Characterizing Complexity: Metrology Innovations for Next-Gen Logic Nodes

Daniel Schmidt (IBM Research, USA)

[TuC1-2] [Invited] 13:45-14:15

Progress of X-Ray Metrology for Analyzing Device Nanostructures in Advanced Semiconductors

Kazuhiko Omote (Rigaku Corporation, Japan)

[TuC1-3] [Invited] 14:15-14:45

Spatially Coherent Xray Imaging over a Large FOV, High-Resolution, within Seconds

Trevor A. Norman (NeXray Inc., Korea)